



Docket No.: 101361-0043

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Robert P. Dolan, et al.

Application No.: 09/884,451

Group Art Unit: 2823

Filed: June 19, 2001

Examiner: J. Maldonado

For: **SIMOX USING CONTROLLED WATER
VAPOR FOR OXYGEN IMPLANTS**

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Commissioner for Patents
Washington, DC 20231

Dear Sir:

The undersigned Angelo V. Alioto, Vice President of Sales and Marketing at IBIS Technology Corporation, Inc. ("IBIS") of 32A Cherry Hill Drive, Danvers, Massachusetts 01923, a Massachusetts corporation, states the following:

- (a) IBIS is the Assignee of Patent Application Serial No. 09/884,451, entitled "SIMOX using controlled water vapor for oxygen implant," filed on June 19, 2001 as a continuation of Patent Application Serial No. 09/339,633, filed on June 24, 1999, and having the same title. These applications relate to methods of processing a silicon wafer, by utilizing an ion implanter, that lower the defect density of the processed wafers by introducing a fluid other than molecular oxygen into the implantation chamber of the ion implanter followed by implanting ions, such as oxygen, into the wafer.
- (b) IBIS entered into an Agreement with International Business Machines Corporation ("IBM") in 1996, a redacted copy of which is herein enclosed, for testing of oxygen implant systems manufactured by IBIS including an implant system manufactured under the trade designation IBIS 1000. IBM was obligated under the terms of the contract to treat information regarding operation of IBIS implant machines and annealing of implant wafers as confidential.

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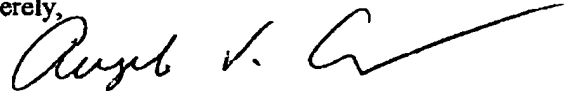
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(c) Pursuant to the Agreement, IBM tested the IBIS 1000 during the time period from October 1996 through, at least, July 1998. The tests included the practice of at least some of the methods claimed in the above-referenced patent applications. IBM provided IBIS feedback regarding the tests.

(d) Throughout the IBM testing period, IBIS considered these tests as experimental use of the methods claimed in the above-referenced applications. The confidentiality agreement between IBIS and IBM were drafted to ensure the confidentiality of this experimental use data.

Dated:

Sincerely,



Angelo V. Alioto
Vice President of Sales and Marketing
IBIS Technology Corporation



International Business Machines Corporation

East Fishkill Facility
1580 Route 52
Hopewell Junction, NY 12533-6531
914 / 894-2121

International Business Machines Corporation (hereinafter called IBM) and IBIS Technology Corporation (hereinafter called IBIS), collectively the Parties, wish to enter into an Agreement that will permit each Party to disclose to the other Party, for a limited period of time, information, some of which may be considered confidential, in order to improve each Party's ability to operate oxygen implant machines.

This letter Agreement sets forth the terms and conditions under which information, including that information considered to be confidential, will be disclosed.

1. For the purposes of this letter Agreement: "IBM Confidential Information" and "IBIS Confidential Information" shall mean that information pertaining to the operation of implant machines for implanting oxygen into silicon wafers and the annealing of implanted wafers, and disclosed, embodied in tangible form and marked as specified below.

If the above terms and conditions are acceptable to IBIS, kindly have both copies of this letter Agreement signed on behalf of IBIS and return one copy of this Agreement to me.

Very truly yours,

INTERNATIONAL BUSINESS
MACHINES CORPORATION

By

M R Polcari
Michael R. Polcari
Director
Silicon Technology

Date

11/1/96

ACCEPTED AND AGREED TO
FOR IBIS TECHNOLOGY
CORPORATION
32 Cherry Hill Drive
Danvers, MA

By

G. Ryding
Geoff Ryding
CEO

Date

10-7-96